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U.S. UTILITY Patent Application

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Ian Latchford Christopher Dennis Bencher Yuxiang Wang Mario Dave Silvetti Photolithography scheme using a silicon containing resist	AP	PLICATION NO. 09/921938	CONT/PRIOR D	CLASS 430	SUBCLASS 3 3	1756 1757	WALKE	
	APPLICANTS	Christoph Yuxiang t Mario Dav	ner Denni Wang ve Silvet	ti		icon conta	aining resist	
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	DRAWINGS			CLAIMS ALLOWED		
DISCLAIMER	Sheets Drwg.	Figs. Drwg.	Print Fig.	Total Claims	Print Claim for O.G.	
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not extend beyond the expiration date of U.S Patent. No.	i i			ISSUE FEE		
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this patent have been disclaimed.	(Legal instrum	ents Examiner)	(Date)			
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